Nanostructured surfaces

Carbonization and formation of metal nanoparticles processes in ion-implanted PMMA

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In the present work, the results of slow positron beam spectroscopy (SPBS) study of carbonization in high-dose $(2.5 \times 10^{16}, 3.75 \times 10^{16}, \text{and } 5.0 \times 10^{16} \text{ ions/cm}^2)$ 40 keV boron-ion-implanted polymethylmethacrylate (B:PMMA) [1] and formation of metal nanoparticles in high-dose $(2.5 \times 10^{16} \text{ and } 1.0 \times 10^{17} \text{ ions/cm}^2)$ 30 keV silver-ion-implanted polymethylmethacrylate (Ag:PMMA) [2] are reviewed. The features between carbonization and formation of metal nanoparticles processes in ion-implanted B:PMMA and Ag:PMMA as revealed from SPBS measurements of *S*(*E*) parameter, SRIM simulation and other proper techniques are considered.

1. *Kavetskyy T., Tsmots V., Kinomura A., Kobayashi Y., Suzuki R., Mohamed H. F. M., Šauša O., Nuzhdin V., Valeev V., Stepanov A. L.* Structural defects and positronium formation in 40 keV B⁺-implanted polymethylmethacrylate // J Phys Chem B.-2014.-**118**.-P. 4194-4200.

2. Kavetskyy T. S., Iida K., Nagashima Y., Kuczumow A., Šauša O., Nuzhdin V., Valeev V., Stepanov A. L. High-dose boron and silver ion implantation into PMMA probed by slow positrons: Comparison between effects of carbonization and formation of metal nanoparticles // Abstracts of 14th International Workshop on Slow Positron Beam Techniques and Applications (SLOPOS 14) (Matsue, Japan, 22-27 May, 2016), in press.